

### IN THE CLAIMS

Claims 2 and 11-19 are pending in this application. Please cancel claims 1 and 3-10 without prejudice or disclaimer, and amend claims 2 and 11 as follows:

1. (Canceled).
2. (Currently Amended) [[A]] An accumulation-mode semiconductor device comprising:
  - a SOI substrate having a surface monocrystalline silicon layer and an insulating layer formed on a base substrate;
  - a source diffusion portion and a drain diffusion portion both having a first conductive type formed in the surface monocrystalline silicon layer of the SOI substrate;
  - a channel portion also formed of said first conductive type and having one end adjacent to the source diffusion portion and the other end adjacent to the drain diffusion portion and
  - a gate insulating film formed on the channel portion, wherein the gate insulating film is a laminated film comprising an insulating film formed on the channel portion and a metal oxide film having a higher dielectric constant than the insulating film.
- 3-10. (Canceled).
11. (Currently Amended) [[A]] An accumulation-mode semiconductor device comprising:
  - a SOI substrate having an insulating layer and a surface monocrystalline silicon layer formed on a base substrate;
  - at least one separation area made from an insulating material formed in the SOI substrate;
  - a first area in which a source diffusion portion and a drain diffusion portion both having a first conductive type are formed in the surface monocrystalline silicon layer of the SOI substrate bounded by the separation area;

a second area which is adjacent to the first area and adjacent to the separation area and in which opposite type source and drain diffusion portions having an opposite conductive type to the first conductive type are formed, wherein

a gate insulating film formed on a channel portion having one end adjacent to the source diffusion portion and the other end adjacent to the drain diffusion portion in the first and second areas,

the gate insulating film comprising a laminated film of an insulating film formed on the channel portion and a metal oxide film having a higher dielectric constant than the insulating film, and

wherein the channel portion of the first area has the first conductive type and the channel portion of the second area has the second conductive type.

12. (Original) The semiconductor device according to claim 2, wherein the channel portion is fully depleted.
13. (Original) The semiconductor device according to claim 2, wherein no junction between the first conductive type and a second conductive type opposite to the first conductive type is formed in the monocrystalline silicon layer.
14. (Original) The semiconductor device according to claim 2, wherein the SOI substrate is a laminated substrate consisting of a first monocrystalline semiconductor layer formed on the substrate through an insulating film and a second monocrystalline semiconductor layer formed on the first monocrystalline semiconductor layer, wherein a first lattice constant of the first monocrystalline semiconductor and a second lattice constant of the second monocrystalline semiconductor differ from each other to form a strained silicon layer in the channel portion.
15. (Original) The semiconductor device according to claim 2, wherein the concentration of an impurity forming the channel portion is lower than the concentration of an impurity forming the source or drain portions.
16. (Original) The semiconductor device according to claim 2, wherein the thickness of the monocrystalline silicon layer is 4 nm or less.

17. (Original) The semiconductor device according to claim 2, wherein the gate insulating film contains a silicon oxy nitride film or silicon nitride film.
18. (Original) The semiconductor device according to claim 2, wherein the gate insulating film contains a metal oxide or metal oxy nitride.
19. (Original) The semiconductor device according to claim 2, wherein the gate insulating film contains an oxide of a metal material selected from the group consisting of aluminum, hafnium and zirconium, an insulating film containing at least one of the oxides of said metal materials, an oxy nitride film of any one of said metal materials, a silicate film, or a laminated film thereof.